IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

Akshey Seghal

Application No.: 10/620,895

Filed: July 16, 2003

For: COMPOSITIONS AND METHOD FOR REMOVING PHOTORESIST AND/OR RESIST RESIDUE AT PRESSURES RANGING FROM AMBIENT TO

SUPERCRITICAL

Confirmation No.: 8934

Group Art Unit: 1746

Examiner: Bibi Sharidan Carrillo

RESPONSE TO OFFICE ACTION MAILED JUNE 28, 2004

353 Sacramento St., Suite 2200 San Francisco, CA 94111 (415) 772-4900

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as First Class Mail in an envelope, addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450 on Sept. 27, 2004.

STALLMAN & POLLOCK LLP

M/S NON-FEE AMENDMENT Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

In response to the Office Action mailed June 28, 2004, please amend the above-identified application as follows:

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks/Arguments begin on page 7 of this paper.

Atty Docket No.: SCP-9410